

ABSTRACT OF THE DISCLOSURE

This invention relates to a scanning exposure apparatus for transferring a pattern of a reticle onto each shot region while synchronously scanning the
5 reticle and the wafer on which a plurality of shots are arrayed. This apparatus includes a reticle stage for moving the reticle, a wafer stage for moving the wafer, and a controller for controlling continuous scanning exposure for the plurality of shot regions so as to
10 assure a setting distance serving as a distance for moving the reticle stage at a uniform velocity in order to guarantee that synchronization error between the reticle stage and wafer stage falls within an allowable range upon accelerating the wafer stage up to a scan
15 speed for scanning exposure. The controller controls the continuous scanning exposure such that the setting distance for the first shot region to be scanned and exposed upon a change in row to which shot regions serving as exposure objects belong is set larger than
20 the setting distance of other shot regions.